

## PATENT ABSTRACTS OF JAPAN

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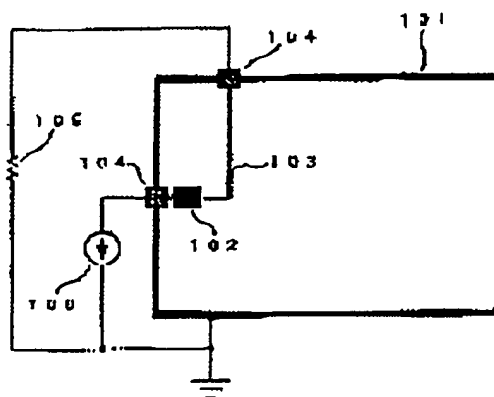
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**(54) MANUFACTURE OF ELECTRON EMISSION SOURCE AND ELECTRON EMISSION SOURCE**

**(57)Abstract:**

**PROBLEM TO BE SOLVED:** To provide a manufacturing method of an electron emission source and the electron emission source which is easily manufactured and excellent in an electron emission characteristic.

**SOLUTION:** A chamber 101 is made to have an He atmosphere of 1 Pa pressure and is arc discharged for one second by making an arc current of a 100A direct current flow, and a negative electrode 102 is locally heated. Thereby a negative electrode material constructing a negative electrode 102 is scattered so as to produce carbon particles formed with a plurality of carbon nano- tubes on the surface thereof. The carbon particles are collected and used as an emitter of an electron emission source.



## LEGAL STATUS

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